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October 5, 2007

#### VIA EMAIL

Brett M. Schuman Morgan Lewis & Bockius LLP One Market Street, Spear Street Tower San Francisco, CA 94105

Re: Alpha & Omega Semiconductor, Ltd. v. Fairchild Semiconductor Corp.

Case No. C 07-2638 JSW (consolidated with Case No. C 07-2664 JSW)

Our File No. 18865P-021600

#### Dear Brett:

Fairchild has retained Dr. Richard Blanchard as a technical expert consultant in this action. During the course of his work, he will need to review documents and other technical information which AOS will likely designate as "Confidential" or "Highly Confidential - Attorneys' Eyes Only" information under the protective order. For this reason, I am writing to place AOS on notice of Fairchild's intent to disclose such information to Dr. Blanchard.

Please find attached Dr. Blanchard's resume which includes a description of his work experience, education, publications, and consulting activities in which he testified at deposition or trial. Additionally, enclosed is a signed undertaking stating that Dr. Blanchard agrees to abide by the terms of the protective order.

We are unable to disclose further information about Dr. Blanchard's consulting activities, as required by the protective order, due to confidentiality agreements with his clients. His work, however, does not pose any actual or potential risk of misuse of AOS's confidential information. We therefore request that AOS permit Dr. Blanchard to have access to AOS's confidential information based on the information we are providing and the information about him which AOS already possesses.

AOS is very familiar with Dr. Blanchard's background and reputation for professionalism and therefore should have no objection to his having access to confidential information. Indeed, AOS deposed him in the *Siliconix v. AOS* patent litigation, and we understand that AOS sought to hire him as an expert consultant in the present action, not knowing that Fairchild had already retained him. Additionally, the information we are providing about his background far exceeds the level of disclosure required by the accompanying protective order to which AOS stipulated in

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the *Siliconix* action. (See separate attachment.) Under that protective order, a party seeking to disclose confidential information needed to disclose only the consultant's name, address, present employer, title, resume, and a signed undertaking. (See *Siliconix v. AOS* protective order at Section 4.1.) No other information was required. Accordingly, the background information we are providing about Dr. Blanchard is more than sufficient.

For the reasons set forth above, we request that AOS permit Dr. Blanchard to review AOS's information designated as "Confidential" and "Highly Confidential - Attorneys' Eyes Only" under the protective order in this action. Please let me know by October 12 whether this is acceptable. If AOS agrees, we suggest the parties file a stipulation and proposed order to modify the protective order in this respect.

Very truly yours,

/s/

Matthew R. Hulse

**Enclosures** 

61170816 v1

## Richard A. Blanchard, Ph.D.

## **Expertise**

- MOS and Bipolar Device Technology
- Semiconductor Device Physics
- Microchip Fabrication & Analysis
- Electronic Systems
- Electrical & Electronic Failures
- CMOS, DMOS & BiCMOS
- Power IC's & Power Electronics
- Printed Circuit Board Manufacturing
- Semiconductor Process & Control
- Semiconductor Process Equipment

### **Professional Summary**

Dr. Blanchard has over 35 years of combined industry, research, academic, and consulting experience. His research covers semiconductor device and electronics design, semiconductor device physics, semiconductor manufacturing processes and equipment, failure analysis, reverse engineering of semiconductor and electronic circuits, and reliability modeling. Dr. Blanchard's work has resulted in more that 120 U.S. issued patents. He has also written or co-authored numerous books and articles in the semiconductor design and process development areas as well as failure analysis.

## **Employment History**

From: 1998 Silicon Valley Expert Witness Group, Inc.

To: Date Mountain View, CA

Position: *Director*, *Advanced Technologies* 

Silicon Valley Expert Witness Group, Inc. (SVEWG) is a high technology, "Silicon Valley" consulting company specializing in expert witness litigation support and technology consulting.

SVEWG has an extensive roster of world-class technology experts used in the defense and promotion of intellectual property rights and other litigation disputes. SVEWG Principals offer extensive in-house technology, legal and business expertise and have direct access to

senior litigation and technology consultants worldwide.

From: 1991 Failure Analysis Associates, Inc. (Now named "Exponent")

To: 1998 Menlo Park, CA

Position: Principal Engineer & Division Manager

Responsible for the Electrical/Electronic Division of Failure Analysis Associates providing consulting services to the electrical

Richard A. Blanchard, Ph.D.

and electronics industry. Specific duties include:

- Semiconductor devices. Failure analysis and reverse engineering of solid-state electronic components and circuits. Semiconductor processing and semiconductor process equipment. Semiconductor manufacturing and process control.
- Failure analysis of electric and electronic systems, subsystems, and components, including causes of electrical fires
- Reliability modeling and lifetime prediction of electrical and electronic systems and subsystems
- Automotive electronics. Design of discrete devices and integrated circuits
- Power Electronics. Power MOS and Smart Power Technologies

1987 From:

1991 To:

**IXYS** Corporation

Position: Senior Vice President

> Responsible for the development of IC products. Established an inhouse CAD capability. Recruited an IC design team and coordinated the definition and development of IXYS ICs. Identified, qualified and monitored the IC foundries that manufactured these circuits. Set up testing capability at IXYS. Coordinated assembly on IC's. Worked on various MOSFET and IGBT device, test, and assembly problems.

From: 1982 Siliconix, Inc.

1987 To:

> Position: Vice President, Engineering

> > Other titles held at Siliconix, Inc. were Engineering Manager (1982-1983) and Director (1983-1984). Responsible for the development of advanced process technology and the design of both discrete devices (JFETs, lateral and vertical DMOS transistors) and integrated circuits (low and high voltage CMOS, D/CMOS and bipolar-JFET). These responsibilities included providing technical and administrative direction to two IC design groups in the United Kingdom and the U.S., one device and process design group and a "quick-turn" processing line. Two CAD groups, one in the U.K. and one in the U.S., and a CAE group developing computer software and hardware for the engineering community rounded out the department. Personally responsible for many key innovations and inventions in power MOS and D/CMOS IC technology and their assembly and test requirements. He submitted approximately 20 patent disclosures while employed at Siliconix, Inc. He holds the two key "trench FET" patents, of which he is the sole inventor.

From: 1976 **Supertex, Inc.** 

To: 1982

Position: Founder and Vice President, MOS Power Products

Responsible for investigation of new semiconductor devices and new technologies. In charge of Power MOS device research, design and development. His work lead to the design and development of both the discrete power MOS device family and the high voltage IC (HVIC) family sold by Supertex, Inc. Responsible for an in-house assembly area as well as engineering aspects of power MOS and HVIC testing.

From: 1976 **Cognition, Inc.** 

To: 1978

Position: Founder and Consulting Engineer

Responsible for developing the process technology for fabricating monolithic silicon pressure sensors. A process line was established for the manufacture of piezoresistive pressure sensors, including the

precision etching of thin silicon diaphragms.

From: 1974 **Foothill College** 

To: 1978

Position: Associate Professor, Assistant Division Chairman, Engineering &

Technology Division

Accomplishments included developing the curriculum for the Semiconductor Technology Program, and establishing a small processing facility for teaching students the fundamentals of semiconductor technology. Supervised enpreyimptely 60 instructions

semiconductor technology. Supervised approximately 60 instructors

in the evening and off-campus programs.

From: 1974 **Independent Consultant** 

To: 1976

Duties: Consultant to the semiconductor industry, including court appointed

"Special Master" in the <u>Fairchild Semiconductor Corporation v.</u>
National Semiconductor Corporation Isoplanar patent suit.

From: 1970 Fairchild Semiconductor

To: 1974 Mountain View, CA

Position: Senior Engineer, Department Manager

Responsible for the fabrication of the integrated circuits in the Polaroid SX-70 camera. Technologies directly related to this work include standard bipolar technology, bipolar- MOS technology, silicon gate technology and flip-chip assembly technology.

### **Deposition and Trial Testimony (Past Five Years)**

<u>Apple Computer, Inc.</u> v. Tatung Co., International Court of Arbitration of the International Chamber of Commerce, Case No. 10099 AER. (D, R)

Anne Camilleri as Guardian for Andrea Camilleri, an incompetent Adult, vs. <u>Costco Companies, Inc., Thompson Merchandising, Everstar Merchandise</u>, So Yang Enterprises Co. Ltd. And Does 1 to 1000. Superior Court of the State of California, County of San Mateo, Case No. 407 06 & Case No. 408 615. (D)

Micrel, Inc. v. Federal Insurance Company, Superior Court of the State of California and Santa Clara County, Case No. CV786627. (D, R)

<u>Sun Microsystems</u> v. Kingston Technology, United States District Court, Northern District of California, Case No. C99-03610VRW. (D, R)

<u>Level One</u> v. Altima, United States International Trade Commission, Washington, D.C., Investigation No. 337-TA-435. (D, R, T)

Optus Networks Pty Ltd CAN 008 570 330 and Ors v. Leighton Contractors Pty Ltd CAN 000 893 667 and Ors, Supreme Court of New South Wales Sydney Registry Common Law Division Construction List, No. 55059 of 1997. (R, T)

<u>Federal Insurance Company</u> v. Metex Corporation, Superior Court of the State of California, County of San Francisco, No. 988899. (D, R)

Pekin Insurance Company and Green Bay Motor Sports, Inc. v. <u>American Suzuki Motor Corporation</u>, Circuit Court of the State of Wisconsin, County of Brown, No. 01-CV-416 (4/2002). (D)

Kenneth Toner and Daniel J. Harper, as Trustee of the Recall Claimants Trust v. Cadet Manufacturing Company, <u>I.R.C.A. S.P.A.</u>, Zoppas Industries S.P.A. and Still-man Heating Products Inc., Superior Court of the State of Washington, County of King, No. 98-2-10876-2SEA (4/2002). (D)

Allen Scott Schneider, Tami Schneider v. <u>Sentry Alarm, Inc.</u>, Sylvester's Alarm, Inc. a.k.a. Sylvester's Security Services, Inc. Automatic Alarm, Inc., Superior Court of the State of California, County of Santa Clara, Case No. CV 795867. (D)

David Bryte, Personal Representative of the Estate of Lova E. Bryte, deceased, et al, plaintiffs v. <u>Sunbeam Corporation</u> & Sears Roebuck and Co., defendants. In the United States District Court for the Northern District of West Virginia, Case No. 2:00-CV-93. (D, R)

SimpleTech, Inc. v. <u>Atmel Corporation</u>, Superior Court of the State of California, County of Santa Clara, Case No. CV 809851 (2004). (D, R)

Pavel Kuzmenko; Karina Kuzmenko and Kristina Kuzmenko v. Morningside Apartments, William R. Canihan, and <u>MacFrugal's Bargain Close Out</u>, Superior Court of the State of California, County of Sacramento, Case No. 01AS00112 (2004). (D)

State Farm Fire & Casualty Insurance Company; as subrogee for Terry Swan, and Terry Swan, individually v. <u>Sears, Roebuck and Co.</u>, a foreign corporation, the United States District Court for the Western District of Washington, Case No. C01-129 (C). (D, R)

Rexford Agin, Susan Agin and Daniel Agin v. <u>Sunbeam Products, Inc.</u>, in the United States District Court for the Southern District of Ohio Eastern Division, Civil Action No. C2030052. (D, R)

Bobby Cook, as Personal Representative of the Estate of Cathy Lynn Cook, Deceased; and Bobby Cook, Individually v. <u>Sunbeam Corporation, Sunbeam Products, Inc.</u>, Wal-Mart Stores, Inc., and Wal-Mart Stores, East, Inc., United States District Court for the Northern District of Alabama Southern Division, Case No. CV-01-B-2000-S. (D, R)

<u>IXYS Corporation</u> v. Advanced Power Technology, Inc., United States District Court for the Northern District of California San Francisco Division, Case No. C 02-3942 MHP. (D, R)

Motorola, Inc. v. Analog Devices, Inc., United States District Court for the Eastern District of Texas Beaumont Division, Civil Action No. 1:03-CV-0131 (RHC). (D, R)

Siliconix Inc., a Delaware corporation v. Alpha and Omega Semiconductor Inc., a California corporation, and Alpha and Omega Semiconductor Limited, a Bermuda corporation, United States District Court for the Northern District of California San Francisco Division, Case No. C03-04803 WHA (Inventor). (D)

Sunex, Inc. v. <u>Omnivision Technologies/Omnivision Technologies, Inc.</u>, a Delaware Corporation v. Sunex, Inc, Superior Court of the State of California County of San Diego, North County Division, Case No. 031205. (D)

<u>Fujitsu Limited</u> v. Cirrus Logic, Inc., Amkor Technology, Inc., Sumitomo Bakelite Co., Ltd., and Sumitomo Plastics America, Inc., Superior Court of the State of California County of Santa Clara, Case. No. 1-03-CV-009885. (D)

<u>Silicon Laboratories, Inc.</u> v. Ali Niknejad & Axiom Microdevices, Inc., United States District Court for the Western Division of Texas Austin Division, Civil Action No. A-04-CA-155-SS. (D, T)

Joel R. Bertelson, Daniel E. Mendl, Daniel E. Mendl as Trustee, The Bigfoot Ranch, II, Inc., Daniel E. Mendl as Attorney In Fact for Katherine Hope Bertelson and Union Mutual Fire Insurance Co. and New England Guaranty Insurance Co., Inc. v. Sunbeam Products, Inc. and The Allen Agency, Inc., Superior Court of the State of Vermont Chittenden County, SS, Docket No. S0312-04 CnC. (D)

Micrel Inc. v. <u>Monolithic Power Systems</u>, Michael R. Hsing, James C. Moyer, and DOES 1-20 inclusive, Unites States District Court for the Northern District of California San Francisco Division, Case No. C04-04770 JSW (JCS). (D)

<u>Siliconix, Inc.</u> v. Denso Corporation, United States District Court for the Northern District of California, San Francisco Division, Case No. C05-01507 WHA and Consolidated Actions Nos. C04-00344 WHA and C05-03617 WHA. (D)

<u>Tessera, Inc.</u> v. Micron Technology, Inc. and Infineon, United States District Court for the Eastern District of Texas Marshall Division, Case No. 2-05CV94. (R)

<u>Siliconix, Inc.</u> v. Semiconductor Components Industries, LLC d/b/a On Semiconductor, American Arbitration Association, Phoenix, Arizona, Case No. 76 133 Y 00327 05 DEAR. (D)

John Rumans, Jeanne Rumans and Jessica Rumans v. <u>Sunbeam Products, Inc.</u>, United States District Court for the Western District of Missouri Western Division, Case No. 05-1226-CV-W-HFS. (D)

Markel American Insurance Company, Insurance Company of North America and State Farm Fire and Casualty Company v. Cadet Heater Manufacturing Company v. <u>ZIMM</u> (Third-Party Defendants), United States District Court for the District of Oregon, Case No. 3:05-CV-1188 KI (Lead Case). (D, R)

Verigy US, Inc. v. Romi Omar Mayder, Wesley Mayder, <u>Silicon Test Systems, Inc.</u>, and Silicon Test Solutions, LLC, United States District Court for the Northern District of California San Jose Division, Case No., C07-04330 RMW (HRL). (D)

Nathan J. Sheridan v. Fladeboe Volkswagen, Inc., <u>Volkswagen of America, Inc.</u>, Superior Court of the State of California for the County of Orange, Case No. 06CC09510. (D)

D = Deposition

R = Report

T = Testimony in Court

#### **Patents**

<u>Patent Number</u>	Date Issued	<u>Title</u>
7,244,970	07/17/2007	Low Capacitance Two-Terminal Barrier Controlled TVS Diodes
7,224,027	05/29/2007	High Voltage Power MOSFET Having a Voltage Sustaining Region
		that Includes Doped Columns Formed by Trench Etching and
		Diffusion from Regions of Oppositely Doped Polysilicon
7,202,494	04/10/2007	FinFET Including a Supperlattice

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7,199,427	04/03/2007	DMOS Device with a Programmable Threshold Voltage
7,138,289	11/21/2006	Technique for Fabricating Multilayer Color Sensing Photodetectors
7,094,621	08/22/2006	Fabrication on diaphragms and 'Floating' Regions of Single Crystal
.,	00,, -000	Semiconductor for MEMS Devices
7,091,552	08/15/2006	High Voltage Power MOSFET Having a Voltage Sustaining Region
.,	00, -0, -00	that Includes Doped Columns Formed by Trench Etching and Ion
		Implantation
7,084,455	08/01/2006	Power Semiconductor Device Having a Voltage Sustaining Region that
,,001,100	00,01,2000	Includes Terraced Trench with Continuous Doped Columns Formed in
		an Epitaxial Layer
7,067,376	06/27/2006	High Voltage power MOSFET Having Low On-Resistance
7,061,072	06/13/2006	Integrated Circuit Inductors Using Driven Shields
7,023,069	04/04/2006	Method for Forming Thick Dielectric Regions Using Etched Trenches
7,019,360	03/28/2006	High Voltage Power MOSFET Having a Voltage Sustaining Region
,,012,000	00,20,200	that Includes Doped Columns Formed by Trench Etching Using an
		Etchant Gas that is also a Doping Source
7,015,104	03/21/2006	Technique for Forming the Deep Doped Columns in Superjunction
6,992,350	01/31/2006	High Voltage Power MOSFET Having Low On-Resistance
6,949,432	09/27/2005	Trench DMOS Transistor Structure Having a Low Resistance Path to a
, ,		Drain Contact Located on an Upper Surface
6,921,938	07/26/2005	Double Diffused Field Effect Transistor Having Reduced On-
, ,		Resistance
6,906,529	06/14/2005	Capacitive Sensor Device With Electrically Configurable Pixels
6,882,573	04/19/2005	DMOS Device with a Programmable Threshold Voltage
6,861,337	03/01/2005	Method for Using a Surface Geometry for a MOS-Gated Device in the
		Manufacture of Dice Having Different Sizes
6,812,526	11/02/2004	Trench DMOS Transistor Structure Having a Low Resistance Path to a
		Drain Contact Located on an Upper Surface
6,812,056	11/02/2004	Technique for Fabricating MEMS Devices Having Diaphragms of
		"Floating" Regions of Single Crystal Material
6,794,251	09/21/2004	Method of Making a Power Semiconductor Device
6,790,745	09/14/2004	Fabrication of Dielectrically Isolated Regions of Silicon in a Substrate
6,777,745	08/17/2004	Symmetric Trench MOSFET Device and Method of Making Same
6,750,523	06/15/2004	Photodiode Stacks for Photovoltaic Relays and the Method of
		Manufacturing the Same
6,750,104	06/15/2004	High Voltage Power MOSFET Having a Voltage Sustaining Region
		that Includes Doped Columns Formed by Trench Etching Using an
		Etchant Gas that is also a Doping Source
6,734,495	05/11/2004	Two Terminal Programmable MOS-Gated Current Source
6,730,963	05/04/2004	Minimum Sized Cellular MOS-Gated Device Geometry
6,724,044	04/20/2004	MOSFET Device Having Geometry that Permits Frequent Body
		Contact
6,724,039	04/20/2004	Semiconductor Device Having a Schottky Diode

6,713,351	03/30/2004	Double Diffused Field Effect Transistor Having Reduced On- Resistance
6,710,414	03/23/2004	Surface Geometry for a MOS-Gated Device that Allows the Manufacture of Dice Having Different Sizes
6,710,400	03/23/2004	Method for Fabricating a High Voltage Power MOSFET Having a Voltage Sustaining Region that Includes Doped Columns Formed by Rapid Diffusion
6,689,662	02/10/2004	Method of Forming a Higher Voltage Power MOSFET Having Low On-Resistance
6,686,244	02/03/2004	Power Semiconductor Device Having a Voltage Sustaining Region that Includes Doped Columns Formed with a Single Ion Implantation Step
6,660,571	12/09/2003	High Voltage Power MOSFET Having Low On-Resistance
6,656,797	12/02/2003	High Voltage Power MOSFET Having a Voltage Sustaining Region that Includes Doped Columns Formed by Trench Etching and Ion Implantation
6,649,477	11/18/2003	Method for Fabricating a Power Semiconductor Device Having a Voltage Sustaining Layer with a Terraced Trench Facilitating Formation of Floating Islands
6,627,949	09/30/2003	High Voltage Power MOSFET Having Low On-Resistance
6,624,494	09/23/2003	Method for Fabricating a Power Semiconductor Device Having a Floating Island Voltage Sustaining Layer
6,621,107	09/16/2003	Trench DMOS Transistor with Embedded Trench Schottky Rectifier
6,593,619	07/15/2003	High Voltage Power MOSFET Having Low On-Resistance
6,593,174	07/15/2003	Field Effect Transistor Having Dielectrically Isolated Sources and Drains and Method for Making Same
6,576,516	06/10/2003	High Voltage Power MOSFET Having a Voltage Sustaining Region that Includes Doped Columns Formed by Trench Etching and Diffusion from Regions of Oppositely Doped Polysilicon
6,566,201	05/20/2003	Method for Fabricating a High Voltage Power MOSFET Having a Voltage Sustaining Region that Includes Doped Columns Formed by Rapid Diffusion
6,538,279	03/25/2003	High-Side Switch With Depletion-Mode Device
6,492,663	12/10/2002	Universal Source Geometry for MOS-Gated Power Devices
6,479,352	11/12/2002	Method of Fabricating High Voltage Power MOSFET Having Low On-Resistance
6,472,709	10/29/2002	Trench DMOS Transistor Structure Having a Low Resistance Path to a Drain Contact Located on an Upper Surface
6,468,866	10/22/2002	Single Feature Size MOS Technology Power Device
6,465,304	10/15/2002	Method for Fabricating a Power Semiconductor Device Having a Floating Island Voltage Sustaining Layer
6,432,775	08/13/2002	Trench DMOS Transistor Structure Having a Low Resistance Path to a Drain Contact Located on an Upper Surface
6,420,764	07/16/2002	Field Effect Transistor Having Dielectrically Isolated Sources and

		Drains and Methods for Making Same
6,403,427	06/11/2002	Field Effect Transistor Having Dielectrically Isolated Sources and
, ,		Drains and Method for Making Same
6,399,961	06/04/2002	Field Effect Transistor Having Dielectrically Isolated Sources and
		Drains and Method for Making Same
6,369,426	04/09/2002	Transistor with Integrated Photodetector for Conductivity Modulation
6,368,918	04/09/2002	Method of Fabricating an Embedded Flash EEPROM with a Tunnel
		Oxide Grown on a Textured Substrate
6,331,794	12/18/2001	Phase Leg with Depletion-mode Device
6,316,336	11/13/2001	Method for Forming Buried Layers With Top-Side Contacts and the Resulting Structure
6,291,845	19/18/2001	Fully-Dielectric-Isolated FET Technology
6,272,050	08/07/2001	Method and Apparatus for Providing an Embedded Flash-EEPROM Technology
6,239,752	05/29/2001	Semiconductor Chip Package that is also an Antenna
6,225,662	05/01/2001	Semiconductor Structure with Heavily Doped Buried Breakdown Region
6,215,170	04/10/2001	Structure for Single Conductor Acting as Ground and Capacitor Plate
, ,		Electrode Using Reduced Area
6,198,114	03/06/2001	Field Effect Transistor Having Dielectrically Isolated Sources and
		Drains and Method for Making Same
6,069,385	05/30/2000	Trench MOS-Gated Device
6,064,109	05/16/2000	Ballast Resistance for Producing Varied Emitter Current Flow Along the Emitter's Injecting Edge
6,046,473	04/04/2000	Structure and Process for Reducing the On-Resistance of MOS-Gated Power Devices
6,011,298	01/04/2000	High Voltage Termination with Buried Field-Shaping Region
5,985,721	11/16/1999	Single Feature Size MOS Technology Power Device
5,981,998	11/09/1999	Single Feature Size MOS Technology Power Device
5,981,318	11/09/1999	Fully-dielectric-isolated FET Technology
5,960,277	09/28/1999	Method of Making a Merged Device with Aligned Trench FET and
		Buried Emitter Patterns
5,897,355	05/27/1999	Method of Manufacturing Insulated Gate Semiconductor Device to Improve Ruggedness
5,869,371	02/09/1999	Structure and Process for Reducing the On-Resistance of MOS-gated
		Power Devices
5,856,696	01/05/1999	Field Effect Transistor Having Dielectrically Isolated Sources and Drains
5,821,136	10/13/1998	Inverted Field-Effect Device with Polycrystalline Silicon/Germanium Channel
5,801,396	09/01/1998	Inverted Field-Effect Device with Polycrystalline Silicon/Germanium Channel
5,798,549	08/25/1998	Conductive Layer Overlaid Self-Aligned MOS-Gated Semiconductor

		Devices
5,773,328	06/30/1998	Method Of Making A Fully-Dielectric-Isolated Fet
5,756,386	05/26/1998	Method of Making Trench MOS-Gated Device with A Minimum
-,,		Number of Masks
5,710,443	01/20/1998	Merged Device with Aligned Trench Fet and Buried Emitter Patterns
5,708,289	01/13/1998	Pad Protection Diode Structure
5,701,023	12/23/1997	Insulated Gate Semiconductor Device Typically Having Subsurface-
		Peaked Portion of Body Region For Improved Ruggedness
5,691,555	11/25/1997	Integrated Structure Current Sensing Resistor For Power Devices
		Particularly For Overload Self-Protected Power MOS Devices
5,668,025	09/16/1997	Method of Making a FET with Dielectrically Isolated Sources and
		Drains
5,663,079	09/02/1997	Method of Making Increased Density MOS-Gated Semiconductor
		Devices
5,648,670	07/15/1997	Trench MOS-Gated Device with a Minimum Number of Masks
5,640,037	06/17/1997	Cell with Self-Aligned Contacts
5,637,889	06/10/1997	Composite Power Transistor Structures Using Semiconductor Materials
		With Different Bandgaps
5,589,415	12/31/1996	Method For Forming a Semiconductor Structure with Self-Aligned
		Contacts
5,576,245	11/19/1996	Method of Making Vertical Current Flow Field Effect Transistor
5,574,301	11/12/1996	Vertical Switched-Emitter Structure with Improved Lateral Isolation
5,528,063	06/18/1996	Conductive-Overlaid Self-Aligned MOS-Gated Semiconductor
		Devices
5,485,027	01/16/1996	Isolated DMOS IC Technology
5,298,781	03/29/1994	Vertical Current Flow Field Effect Transistor with Thick Insulator
		Over Non-Channel Areas
5,237,481	08/17/1993	Temperature Sensing Device for Use in a Power Transistor
5,218,228	06/08/1993	High Voltage MOS Transistors with Reduced Parasitic Current Gain
5,164,325	11/17/1992	Method of Making a Vertical Current Flow Field Effect Transistor
5,156,989	10/20/1992	Complementary Isolated DMOS IC Technology
5,132,235	07/21/1992	Method for Fabricating a High Voltage MOS Transistor
5,034,785	07/23/1992	Planar Vertical Channel DMOS Structure
4,983,535	01/08/1991	Vertical DMOS Transistor Fabrication Process
4,978,631	12/18/1990	Current Source with a Process Selectable Temperature Coefficient
4,958,204	09/18/1990	Junction Field-Effect Transistor with a Novel Gate
4,956,700	19/11/1990	Integrated Circuit with High Power, Vertical Output Transistor Capability
4,952,992	08/28/1990	Method and Apparatus for Improving the On-Voltage Characteristics
		of a Semiconductor Device
4,929,991	05/29/1990	Rugged Lateral DMOS Transistor Structure
4,920,388	04/24/1990	Power Transistor with Integrated Gate Resistor
4,916,509	04/10/1990	Method for Obtaining Low Interconnect Resistance on a Grooved

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		Surface and the Resulting Structure
4,914,058	04/03/1990	Grooved DMOS Process with Varying Gate Dielectric Thickness
4,896,196	01/23/1990	Vertical DMOS Power Transistor with an Integral Operating Condition
		Sensor
4,893,160	01/09/1990	Method for Increasing the Performance of Trenched Devices and the
		Resulting Structure
4,868,537	09/19/1989	Doped SiO <sub>2</sub> Resistor and Method of Forming Same
4,851,366	07/25/1989	Method for Providing Dielectrically Isolated Circuit
4,845,051	07/04/1989	Buried Gate JFET
4,832,586	05/30/1989	Dual-Gate High Density FET
4,827,324	05/02/1989	Implantation of Ions into an Insulating Layer of Increase Planar PN
		Junction Breakdown Voltage
4,824,795	04/25/1989	Method for Obtaining Regions of Dielectrically Isolated Single Crystal
		Silicon
4,813,882	03/28/1989	Power MOS Transistor with Equipotential Ring
4,799,100	01/17/1989	Method and Apparatus for Increasing Breakdown of a Planar Junction
4,798,810	01/17/1989	Method for Manufacturing a Power MOS Transistor
4,794,436	12/27/1988	High Voltage Drifted-Drain MOS Transistor
4,791,462	12/13/1988	Dense Vertical J-MOS Transistor
4,774,196	09/27/1988	Method of Bonding Semiconductor Wafers
4,767,722	08/30/1988	Method for Making Planar Vertical Channel DMOS Structures
4,759,836	07/26/1988	Ion Implantation of Thin Film CrSi <sub>2</sub> and SiC Resistors
4,707,909	11/24/1987	Manufacture of Trimmable High Value Polycrystalline Silicon
		Resistors
4,682,405	07/28/1987	Method for Forming Lateral and Vertical DMOS Transistors
4,402,003	08/30/1983	Composite MOS/Bipolar Power Device
4,398,339	08/16/1983	Fabrication Method for High Power MOS Device
4,393,391	07/12/1988	Power MOS Transistor With a Plurality of Longitudinal Grooves to
		Increase Channel Conducting Area
4,345,265	08/17/1982	MOS Power Transistor with Improved High-Voltage Capability
4,344,081	08/10/1982	Combined DMOS and a Vertical Device and Fabrication Method
		Therefore
4,145,703	03/20/1979	High Power MOS Device and Fabrication Method Therefore

## **Education**

1982	Stanford University	Ph.D., Electrical Engineering
	•	Thesis: "Optimization of Discrete High Power MOS Transistors."
1970	M.I.T.	MSEE
		Thesis: "The Use of a Thermal Feedback Mechanism in Power
		Transistor Structures."
1968	M.I.T.	BSEE

Resume of Richard A. Blanchard, Ph.D.

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Resume of Richard A. Blanchard, Ph.D.

#### **Professional Associations and Achievements**

- Senior Member, Institute of Electrical and Electronics Engineers
- Member, Electronic Device Failure Analysis Society
- Member, International Microelectronics & Packaging Society
- Member, American Vacuum Society
- Member, National Fire Protection Association
- Court Appointed Special Master

For more information please contact:

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1 2 3 4 5 6 7	QUINN EMANUEL URQUHART OLIVER & HEDGES, LLP David Eiseman (Bar No. 114758) Albert P. Bedecarré (Bar No. 148178) Patrick C. Doolittle (Bar No. 203659) Daniel N. Kassabian (Bar No. 215249) 50 California Street, 22nd Floor San Francisco, California 94111 Telephone: (415) 875-6600 Facsimile: (415) 875-6700  Attorneys for Plaintiff Siliconix incorporated	ORRICK, HERRINGTON & SUTCLIFFE LLP G. Hopkins Guy, III (Bar No. 124811) Stephen N. Adams (Bar No. 141956) Duo Chen (Bar No. 220675) 1000 Marsh Road Menlo Park, California 94025 Telephone: (650) 614-7400 Facsimile: (650) 614-7401  Attorneys for Defendant Alpha and Omega Semiconductor Incorporated and Alpha And Omega Semiconductor Limited
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9	UNITED STAT	ES DISTRICT COURT
10	NORTHERN DIST	TRICT OF CALIFORNIA
11	SAN FRAN	CISCO DIVISION
12		
13	SILICONIX INCORPORATED, a Delaware corporation,	CASE NO. C 03-4803 WHA
14	Plaintiff,	
15	V.	
16	ALPHA AND OMEGA	STIPULATED PROTECTIVE ORDER
17	SEMICONDUCTOR INCORPORATED, a California corporation, and ALPHA AND	
18	OMEGA SEMICONDUCTOR LIMITED, a Bermuda corporation,	
19 20	Defendants.	
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Pursuant to Federal Rule of Civil Procedure 26, and it appearing that discovery in the above-entitled action will involve the disclosure of confidential information, it is hereby stipulated by and between the Parties through their respective counsel and ordered that the following Protective Order be entered to give effect to the terms and conditions set forth below.

- 1.0 Definitions
  - 1.1 "Siliconix" means Siliconix incorporated.
- 1.2 "AOS" means Alpha and Omega Semiconductor Incorporated and Alpha and Omega Semiconductor Limited.
- 1.3 "Designating Party" means Siliconix or AOS or any non-party producing documents or information under this Protective Order.
  - 1.4 "Receiving Party" means Siliconix or AOS.
- 1.5 "Protected Information" includes the following categories of information, and shall include documents produced during discovery, answers to interrogatories, responses to requests for admission, depositions, hearing or trial transcripts, and tangible things, the information contained therein and all copies, abstracts, excerpts, analyses or other writings that contain, reflect or disclose such information whether contained in attorney work product or not.
- 1.5.1 "Confidential" designates Protected Information that a Designating Party believes to be of a proprietary business or technical nature and not readily available to competitors, potential competitors, and/or other third parties.
- 1.5.2 "Confidential Attorneys' Eyes Only" designates Protected Information that the Designating Party reasonably believes is "Confidential" information within the meaning of Section 1.5.1, the disclosure of which is likely to cause harm to the competitive position of the Designating Party. Such information may fall into one or more of the following categories:
  - 1.5.2.1 Future Business Plans
  - 1.5.2.2 Current Business Plans
  - 1.5.2.3 New Product Development

1	1.5.2.4	New Business Development (for old products)
2	1.5.2.5	Trade Secrets (as defined by California law)
3	1.5.2.6	Proprietary Engineering Information (not generally
4		available to the public)
5	1.5.2.7	Computer Source Code or Product Designs
6	1.5.2.7	Competitor Market Analysis
7	1.5.2.8	Customer Lists
8	1.5.2.9	Internal Financial/Accounting Information
9	1.5.2.10	Operations Information
10	1.5.2.11	Distributor Agreements
11	1.5.2.12	License Agreements
12	1.5.2.13	Foundry Agreements
13	1.5.2.14	Development Agreements
14	1.5.2.15	Agreements with Sales Representatives
15	1.5.2.16	Prices Charged to Distributors and/or Customers
16	1.5.2.17	Business Relationships with Third Parties
17	1.5.2.18	Current Product Development and Production
18	1.5.2.19	Costs Related Information
19	1.5.3 Pr	otected Information shall not include: information that is in the
20	public domain at the time of disc	closure (except such information in the public domain which may
21	be treated as a trade secret due to	the effort involved in collecting and maintaining such
22	information); information which	after disclosure is published or becomes part of the public
23	domain through no fault of a Par	ty receiving information under this Protective Order, but only
24	after it is published or comes int	o the public domain (subject to the same trade secret exclusion
25	stated above): information that is	s in the possession of a Party receiving such information without

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any confidentiality obligations at the time of disclosure; information independently derived by a

Party receiving Protected Information without reference to any Protected Information, as

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1	evidenced by documentation; or information disclosed by a third party having the legal right to do		
2	so.		
3	1.6 "Document" shall have the meaning ascribed to it in Federal Rule of Civil		
4	Procedure Rule 34(a).		
5	1.7 "Employees" means regular full or part-time employees and also temporar	у	
6	personnel who are providing secretarial, clerical and/or administrative services only of the		
7	designated employer.		
8	2.0 Designations of Protected Information		
9	2.1 Each Designating Party who produces or discloses any material that the		
10	Designating Party reasonably believes to contain or reveal Protected Information may designate		
11	the same Confidential, or Confidential – Attorneys' Eyes Only.		
12	2.2 Documents may be designated as Confidential only if, prior to production,	,	
13	the document is clearly marked with a legend which states:		
14	CONFIDENTIAL		
15	2.3 Documents may be designated as Confidential – Attorneys' Eyes Only		
16	only if, prior to production, the document is clearly marked with a legend which states:		
17	CONFIDENTIAL – ATTORNEYS' EYES ONLY		
18	2.4 An answer to an Interrogatory or Request for Admission may be designate	d	
19	as the appropriate category of Protected Information by a statement made therein.		
20	2.5 A deposition transcript or a portion thereof may be designated as the		
21	appropriate category of Protected Information by so designating on the record at the deposition o	r	
22	designating any portion of the transcript as "Confidential" or "Confidential – Attorneys' Eyes		
23	Only" within thirty (30) days following the mailing of the transcript or videotape by the court		
24	reporter or videographer. Such notice thereof shall be made in writing to the reporter, with copies		
25	to all other counsel, designating the portions of the transcript or videotape that contain Protected		
26	Information as either Confidential or Confidential – Attorneys' Eyes Only, and directing the		

reporter to mark that portion of the transcript or videotape accordingly. Until expiration of the

thirty day period specified in this Section 2.5, all deposition transcripts and/or videotapes shall be considered and treated as Confidential – Attorneys' Eyes Only.

- 2.6 Counsel of record shall exert their best efforts to raise claims of confidentiality prior to the disclosure of Protected Information.
- 2.7 Notwithstanding the provisions of Sections 2.2 2.6 of this Protective Order, failure of counsel to designate and/or mark any Protected Information as "Confidential" or "Confidential Attorneys' Eyes Only" as provided above shall not preclude the disclosing Party from thereafter in good faith making such a designation and requesting the Receiving Party to so mark and treat such Protected Information so designated. After such designation, such Protected Information shall be fully subject to this Protective Order and treated thereafter according to the new or corrected designation subject to any objection procedure provided herein. The Receiving Party, however, shall incur no liability for disclosures made prior to notice of such designation. The Parties shall confer in good faith to correct the designation and shall take all necessary steps to prevent further dissemination of the subject materials.
  - 3.0 Disclosure of Protected Information
- 3.1 Information designated "Confidential" may only be disclosed to the following persons:
- 3.1.1 outside counsel of record for Siliconix or AOS in this Action and the Employees of outside counsel of record ("Outside Counsel") who are assisting in this litigation and whose duties require access to Protected Information;
- 3.1.2 independent experts and/or consultants retained by counsel of record for Siliconix or AOS, subject to the provisions of Section 4.0 of this Protective Order;
- 3.1.3 in-house attorneys for each Party, and Employees who are assisting such in-house attorneys in this litigation in filing and/or administrative duties and whose duties require access to Protected Information;
- 3.1.4 Employees or representatives of each Party who are necessary to the Party's preparation and pursuit of claims and defenses in this action;

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- 3.1.5 third parties specifically retained to assist outside counsel in copying or computer coding of documents, but only for purposes of copying or computer coding Protected Information;
- 3.1.6 qualified persons taking or recording testimony involving Protected Information and their Employees whose duties require access to Protected Information; and
  - 3.1.7 the Court and the Court's staff; and
  - 3.1.8 such other persons as the Parties agree to in writing prior to any disclosure of Protected Information.
- 3.2 Information designated Confidential – Attorneys' Eyes Only, including copies thereof, extracts therefrom, compilations and/or summaries thereof and any information therein, may only be disclosed to the following persons: persons falling within the categories specified in Sections 3.1.1, 3.1.2, 3.1.5, 3.1.6, and 3.1.7 of this Protective Order, but shall in no case be disclosed to persons who are involved in competitive decision making or intellectual property licensing decisions for Siliconix or AOS, or to persons who are currently prosecuting, supervising, advising or assisting in any way in the preparation and/or prosecution of any new or pending patent application, continuation, divisional, renewal, substitute or convention application relating to field-effect transistors ("FETs"), or any portion thereof, whether design or utility, whether in the United States or abroad (including applications filed under the Patent Cooperation Treaty), whether or not claiming priority from the patents asserted in this litigation or any foreign counterpart thereof, on behalf of themselves, their employer, any Party to this litigation or any third party (hereafter "Prosecution Counsel" or "Prosecution Consultant"), and further provided that such persons shall not during the pendency of, and for a period of one year following the conclusion of this action (including any appeals), engage in any such prosecution, supervision, advice or assistance in any way in the preparation and/or prosecution of any new patents or patent applications, including provisional patent applications relating to FETs.
- 3.3 Protected Information shall not be made available to any person except as authorized under this Protective Order, and no person identified in Sections 3.1.2, and 3.1.5 shall have access to Protected Information without having first read, acknowledged and agreed in

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26 27 28 writing (in the form of the Declaration for Protective Order attached hereto as Exhibit A) to be bound by this Protective Order. A file of all such written acknowledgments shall be maintained by the Party obtaining them, and copies of such written acknowledgments shall be provided to all counsel of record upon request at the conclusion of this action or if circumstances arise which create reasonable concern over the adherence to this Protective Order.

- 3.4 Each individual who receives any materials designated as "Confidential" or "Confidential – Attorney's Eyes Only" hereby agrees to subject himself or herself to the jurisdiction of this Court for purposes of any proceedings relating to the performance under, compliance with or violation of this Protective Order.
- 3.5 If the recipient of any Protected Information learns that, by inadvertence or otherwise, it has disclosed Protected Information to any person or in any circumstance not authorized under this Protective Order, the Receiving Party must immediately (a) notify in writing the Designating Party of the unauthorized disclosures, (b) use its best efforts to retrieve all copies of the Protected Information, (c) inform the person or persons to whom unauthorized disclosures were made of all the terms of this Order, and (d) request such person or persons to execute the declaration and undertaking in the form attached hereto as Exhibit A.
  - 4.0 Objections to Disclosures
- 4.1 Not less than ten (10) days prior to the initial disclosure of Protected Information to any person falling under the provisions of Sections 3.1.2 of this Protective Order, the Party planning to make such disclosure shall serve (by facsimile and mail) the name, address, present employer, title, resume, and a signed Declaration in the form of Exhibit A of the proposed recipient on the Designating Party (and to the opposing Party, if the Designating Party is other than Siliconix or AOS).
- 4.2 Within the ten (10) day period before disclosure of the Protected Information to the proposed recipient, the Party or non-Party whose Protected Information is concerned may serve (by facsimile and mail) a written objection to disclosure to such person. Such an objection shall stay disclosure to the proposed recipient. Failure to serve a written notice of objection within ten (10) days shall be deemed approval of a proposed recipient.

- 4.3 If a written objection is served pursuant to Section 4.2, the Parties shall attempt to resolve the objection by meeting and conferring within ten (10) days of service of the written objection. If the objection is not resolved by meeting and conferring, the Party seeking to prevent disclosure shall file a motion, to be heard on the earliest date available. Failure to file such a motion within ten (10) days of meeting and conferring or at the conclusion of the ten-day period to meet and confer shall preclude a Party from objecting to the disclosure of Protected Information to the person to whom the objection is directed. The disclosure of Protected Information to such proposed person shall be withheld pending the ruling of the Court on any such motion. On any such motion, the Party seeking to prevent disclosure to a person proposed for approval shall have the burden of proof.
- Party claims that a Designating Party is unreasonably designating certain information as

  Confidential or Confidential Attorneys' Eyes Only, the objecting Party may serve a captioned notice of objection on the Designating Party and all Parties, identifying with particularity the items to which the designation is challenged, stating the basis for each challenge, and proposing a new designation for each item. If the Designating Party does not re-designate the material within ten (10) days after service of such notice, the objecting Party may file and serve a motion for an order that the material be re-designated. On any such motion, the Party seeking to prevent re-designation shall have the burden of proof. The original designation shall remain effective until three (3) business days after an Order is entered re-designating the materials. The Court may award sanctions on any motion concerning the challenge of a designation if the Court finds that any Designating Party's or Receiving Party's position was taken without reasonable justification.

### 5.0 Use of Protected Information

5.1 Protected Information disclosed pursuant to this Protective Order shall, unless otherwise ordered by this Court, be used by a recipient thereof solely for the purpose of this Action and not for any other action or for any business or competitive purposes or for any other reason. Protected Information shall not be used for any purposes other than in the

- 5.2 No person shall disclose to anyone not specified in Section 3.0 of this Protective Order any Protected Information without prior written consent of the Designating Party or further Order of this Court.
  - 6.0 Depositions Involving Protected Information
- 6.1 At any deposition session, when counsel of record for a Party deems that a question and/or the answer to a question will result in the disclosure of Protected Information, counsel may designate as Confidential or Confidential Attorneys' Eyes Only the portion of the transcript or videotape containing such question or answer.
- 6.2 Any portion of a transcript designated as Confidential or Confidential Attorneys' Eyes Only Protected Information shall be transcribed separately from the remainder of the transcript of the deposition and designated in the manner set forth in Section 2.0 of this Protective Order.
- 6.3 During the portion of a deposition in which Protected Information will be disclosed, counsel of record for the Designating Party may request that all persons other than the individuals specified in Section 3.1 (for Confidential Protected Information) or Section 3.2 (for Confidential Attorneys' Eyes Only Protected Information) leave the deposition room prior to disclosure of Protected Information. The failure of such other persons to comply with a request of this type shall constitute substantial justification for counsel of record to advise the witness not to answer the question.

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shall, at the option of the Designating Party, either return to the Designating Party or destroy all

Upon final termination of this Action with respect to any Party, that Party

Protected Information in its possession, except such pretrial and trial records as are regularly
maintained by outside counsel in the ordinary course of business, which records must be
protected in conformity with this Protective Order. The termination of proceedings in this Action
shall not thereafter relieve the Parties from the obligation to maintain the confidentiality of all
Protected Information received pursuant to this Protective Order, including the provisions relating
to prosecution of patents set forth in paragraphs 3.2 and 5.1.

- 9.2 This Protective Order is intended to provide a mechanism for the handling of Protected Information, the disclosure or production of which is objected to only on the basis of Confidentiality. Each Party reserves the right to object to any disclosure of information or production of any document it deems Protected Information on any other ground it may deem appropriate. The designation of Protected Information pursuant to this Protective Order shall not create any presumption with respect to the Confidential, proprietary, or trade secret nature of any information, documents or things.
- 9.3 The Parties may, by joint stipulation, apply to amend this Protective Order.

  The amendment shall take effect once the stipulation is entered by the court.
- 9.4 The Court retains jurisdiction to amend this Protective Order without agreement of the Parties and to issue Orders concerning Protected Information disclosed under this Protective Order.
- 9.5 Notwithstanding the foregoing provisions, counsel for either Party may give advice and opinions to his or her client based on his or her evaluation of information disclosed by the opposing Party or a third party and designated as Confidential or Confidential Attorneys' Eyes Only, including for purposes of settlement discussions.
- 9.6 Nothing in this Protective Order shall limit or restrict the manner in which the Parties shall handle their own Protected Information.
- 9.7 Adherence to this Protective Order in no way constitutes an admission by any Party that any information provided in this Action and not subject to this Protective Order is not proprietary or confidential.

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- 9.8 This Protective Order shall not abrogate or diminish any contractual, statutory or other legal obligation or right of any Party or person, nor obligate any Party or person to provide any discovery to which it asserts objections.
- 9.9 Nothing in the foregoing provisions of this Protective Order shall be deemed to preclude any Party from seeking and obtaining, on an appropriate showing, such additional protection with respect to the confidentiality of these proceedings or specific documents or testimony as that Party may deem appropriate, including but not limited to restrictions on public disclosure or disclosure to competitors.
- The terms of this Protective Order shall apply to confidential documents or 9.10 material produced or disclosed by third parties in connection with this action if such third party wishes to designate the document or information Protected Information.
- 9.11 Each Party reserves the right to apply to the Court to modify the terms of this Protective Order in the event that the Party believes that it is necessary. In the event such an application is made, all persons described herein shall be bound by this Protective Order until it is modified by the Court.
- 9.12 The disclosure of Protected Information to any attorney of record shall not prevent or disqualify that attorney of record from representing any Party or any non-party in any future litigation.
- 9.13 If any Party or non-party, having received Protected Information, receives a subpoena or other compulsory process from any other person or entity seeking the production of the Protected Information produced by the Designating Party, counsel for the Designating Party shall be notified in writing immediately and in no event more than three (3) court days after the receipt of the subpoena or other compulsory process and such notification shall include copies of the subpoena or compulsory process. Absent the consent of the Designating Party, the Party or person receiving such subpoena or compulsory process shall refrain to the fullest extent permissible under law from producing the subpoenaed Protected Information. The Party or person receiving such subpoena or compulsory process also must immediately inform in writing the party who caused the subpoena or Order to issue in the other litigation that some or all the

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1	material covered by the subpoena or Order is the	subject of this Protective Order. In addition, the	
2	Receiving Party must deliver a copy of this Protective Order promptly to the Party in the other		
3	action that caused the subpoena or Order to issue. The purpose of imposing these duties is to alert		
4	the interested Parties to the existence of this Prot	ective Order and to afford the Designating Party	
5	in this Action an opportunity to try to protect its	confidentiality interests in the court from which	
6	the subpoena or Order issued. The Designating	Party shall bear the full burden and all expenses	
7	of seeking protection in that court of its Protected	d Information, and nothing in these provisions	
8	should be construed as authorizing or encouraging	ng a Party to this Action to disobey a lawful	
9	directive from another court.		
10			
11	Batea: 171aj 1, 2001	INN EMANUEL URQUHART	
12	OI -	LIVER & HEDGES	
13	∥ <b>-</b>	/s/ Daniel N. Kassabian	
14	Atto	Daniel N. Kassabian  orneys for Plaintiff	
15	5111	conix incorporated	
16	Dated: May 4, 2004 OR	RICK, HERRINGTON & SUTCLIFFE LLP	
17			
18	By.	/s/ Stephen N. Adams Stephen N. Adams	
19	Atto	orneys for Defendants ha and Omega Semiconductor Incorporated	
20		Alpha and Omega Semiconductor Limited	
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1	EXHIBIT A			
2	UNITED STATES DISTRICT COURT			
3	NORTHERN DISTRICT OF CALIFORNIA			
4	SAN FRANCISCO DIVISION			
5				
6	SILICONIX INCORPORATED, a Delaware corporation,		Case No. C 03-4803 WHA	
7				
8		Plaintiff,	DECLARATION AND UNDERTAKING	
9	V.	ID ON IDOA	OF	
10	ALPHA AND OMEGA SEMICONDUCTOR INCORPORATED, a California corporation, and ALPHA AND OMEGA SEMICONDUCTOR LIMITED,			
11				
12	a Bermuda	•		
13		Defendants.		
14				
15	I,		, being duly sworn, state that:	
16	1.	My address is		
17	2.	My present employer is		
18	3.	3. My present occupation or job description is		
19				
20				
21	4. I have received a copy of the Stipulated Protective Order entered in the			
22	above-captioned action signed by the Honorable William Alsup on, 2004.			
23	5.	I have carefully read and under	stand the provisions of the Stipulated Protective	
24	Order.			
25	6.	I will comply with and agree to	be bound by all of the provisions of the Stipulated	
26	Protective Order.			
27	7.	I will hold in confidence, will not disclose to anyone not qualified under the		
28	Stipulated Protective Order, and will use only for purposes of the above-captioned action, any			

1 "Confidential," and or "Confidential – Attorneys' Eyes Only" or which is disclosed to me. 2 8. I will return all "Confidential" and "Confidential Attorneys' Eyes Only" which 3 comes into my possession, and documents or things which I have prepared relating thereto, to 4 counsel for the Party by whom I am retained. 9. 5 I understand and acknowledge that violation of this Undertaking or the Stipulated 6 Protective Order may be punishable by Contempt of Court. I hereby submit to the jurisdiction of 7 this Court for the purpose of enforcement of the Stipulated Protective Order in the 8 above-captioned action. 9 I declare under penalty of perjury under the laws of the United States of America that the 10 foregoing is true and correct. Executed this \_\_\_\_\_\_ day of \_\_\_\_\_\_, 200\_\_ in \_\_\_\_\_\_. 11 12 13 14 15 16 17 18 19 20 21 22 23 24 25 26 27 28

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I	EXHIBIT A		
2	ACKNOWLEDGMENT AND AGREEMENT TO BE BOUND		
3	1, Richard A. Blanchard [print or type full name], of 10724 Mora		
4	Or., Los Altos, CA 94024 [print or type full		
5	address], declare under penalty of perjury that I have read in its entirety and understand the Stipulated		
6	Protective Order (the "Order") that was issued by the United States District Court for the Northern		
7	District of California on August 1, 2007 [date] in the case of C 07-02664 JSW		
8			
9	and acknowledge that failure to so comply could expose me to sanctions and punishment in the nature		
10	of contempt. I solemnly promise that I will not disclose in any manner any information or item that is		
11	subject to this Order to any person or entity except in strict compliance with the provisions of this		
12	Order.		
13	I further agree to submit to the jurisdiction of the United States District Court for the		
14	Northern District of California for the purpose of enforcing the terms of this Order, even if such		
15	enforcement proceedings occur after termination of this Action.		
16			
17	Date: August 10, 2007		
18			
19	City and State where sworn and signed: Mt. View, CA		
20	,		
21	Printed name: Richard A. Blanchard		
22	[printed name]		
23	Signature: Kuland A. Blamband		
24	[signature]		
25			
26			
27			
28			